

EAST Search History**EAST Search History (Prior Art)**

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	144678	(fuel near3 (cell structure element device)).ti.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/14 11:33
L2	41952	1 and electrode	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/14 11:34
L3	15046	2 and (oxygen "O.sub.2" "O2")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/14 11:35
L4	3153	3 and (hyooxygen "H.sub.2" "H2")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/14 11:35
L5	1068	4 and (oxygen "O.sub.2" "O2") near3 electrode	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/14 11:36
L7	146	5 and (hyooxygen "H.sub.2" "H2") near3 electrode	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/14 11:36
L8	18222	429/9-19,30-41. ccis.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/14 11:42

L9	3936	8 and (oxygen "O.sub.2" "O2") near3 electrode	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/14 11:42
L10	167	9 and (hyooxygen "H. sub.2" "H2") near3 electrode	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/14 11:43
L11	130	10 and catalyst	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/14 11:43
L13	122	11 and electrolyte	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/14 11:44
L14	46	13 and (oxygen "O.sub.2" "O2") near3 reduct\$3	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/14 11:45
S58	123943	(trench via groove hole recess opening via) with (IDL interlayer inter adj layer insulat \$4 dielectric) with (etching etch etched etch \$3 pattern patterning patten \$3)	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/04/24 12:13

S59	124056	(trench via groove hole recess opening via) with (IDL interlayer inter adj layer insulat \$4 interlevel intermetal dielectric) with (etching etch etched etch\$3 pattern patterning patten \$3)	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/04/24 12:14
S60	123943	(trench via groove hole recess opening via) with (IDL interlayer inter adj layer insulat \$4 dielectric) with (etching etch etched etch \$3 pattern patterning patten \$3)	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/04/25 17:15
S64	1	10/581210	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/14 10:53

12/14/2009 1:03:58 PM

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